	Hits	Search Text	DBs
1	1	same (remov\$4 or ellminat\$4 or dissolv\$4) same (resin\$4 or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
2	1	((object or substrate or wafer) same (resin or photoresist or resist) same cur\$4) and ((stor\$4 near9 (device or container or holder)) same (liquid or solvent or ether or (TPM near6 ether)) same (electrical\$4 or conductivit\$4) same (remov\$4 or eliminat\$4 or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
3	5		
4	19	((object or substrate or wafer) same (resin or photoresist or resist) same cur\$4) and ((stor\$4 near9 (device or container or holder)) same (liquid or solvent or ether or (TPM near6 ether)) same (remov\$4 or eliminat\$4 or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
5	12	ether)) same (remov\$4 or eliminat\$4 or dissolv\$4 or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
6	44	(resin\$4 or photoresist or resist or polymer\$3) same	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

Hi	ts Search Text	DBs
7 15	ether)) same (remov\$4 or dissolv\$4 or develop\$4) same	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
8	0	photoresist or resist or polymer\$3) same (immers\$4 or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
9	0	solubilizss) same (resins4 or photoresist or resist or	

	Hits	Search Text	DBs
10	10	resist or photoresist or resist or polymer\$3) same (conductivit\$4 or electric\$4 or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
11	101	photoresist or resist or polymers3) same (conductivits4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
12	25	pnotoresist or resist or polymers3) same (conductivits4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
13	56	or electric\$4 or conduct\$4 or resistivity or resistivity or resistance or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
14	40	resistivity or resistance or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
15	83	chang\$4 or increas\$4 or vary\$4)	JPO; DERWENT;
16	53	((bath or (storage near9 device) or solution or liquid or solvent) same (resin\$4 or photoresist or resist or polymer\$3) same (conductivit\$4 or electric\$4 or conduct\$4 or resistivity or resistance or impedance) same (alter\$4 or chang\$4 or increas\$4 or vary\$4)	JPO; DERWENT;

	Hits	Search Text	DBs
17	40	resistivity or resistance or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
18	47		US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
19	54	increas\$4 or vary\$4) same	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
20	15	SZI NOT SZO	US-PGPUB; USPAT
21	6	polymer\$3) same (conductivit\$4 or electric\$4 or conduct\$4 or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
22	3	electric\$4 or current) same (polymer\$4 or resin or resist or photoresist) same (LED or (light near5 emit\$5 near6 diode)) same (ammeter or (current near9 meter)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
23	185	or impedance or resistance or electric\$4 or current) same	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
24	266	or impedance or resistance or electric\$4 or current) same	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
25	1		USPAT; EPO; JPO; DERWENT; IBM_TDB
26	7	resist) same (cur\$4 or expos\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
27	10	resist) same (cur\$4 or expos\$4 or irradiat\$4) same laser) and	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
28	11	resist) same (cur\$4 or expos\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
29	55	((object or substrate or wafer or plate or template) same (resin\$4 or photoresist or resist) same (cur\$4 or expos\$4 or irradiat\$4)) and (strip\$4 same (\$3propylene near12 glycol near10 methyl near12 ether))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
30	44	S31 NOT S30	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
31		regigt) game (curs4 or expogs4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
32	113	<pre>irradiat\$4) same (laser near12 (light or UV)) same develop\$4)</pre>	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
33	6	((substrate or wafer) same (resin\$4 or photoresist or resist) same (expos\$4 or irradiat\$4) same (laser near12 (light or UV)) same develop\$4) and (strip\$4 same (resin or photoresist or resist)) and (laser near9 (advantage\$4 or useful or better or good or preferred or prefer\$5) near14 (expos\$4 or irradiat\$4 or illuminat\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
34	30	((substrate or wafer) same (resin\$4 or photoresist or resist) same (expos\$4 or irradiat\$4) same laser) and (strip\$4 same (resin or photoresist or resist)) and (laser near9 (advantage\$4 or useful or better or good or preferred or prefer\$5) near14 (expos\$4 or irradiat\$4 or illuminat\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB